

a high-index first layer, having a refractive index n_1 of between 1.8 and 2.2 and a geometrical thickness e_1 of between 5 and 50 nm;

a low-index second layer, having a refractive index n_2 of between 1.35 and 1.65 and a geometrical thickness e_2 of between 5 and 50 nm;

a high-index third layer, having a refractive index n_3 of between 1.8 and 2.2 and a geometrical thickness e_3 of between 70 and 120 nm;

a low-index fourth layer, having a refractive index n_4 of between 1.35 and 1.65 and a geometrical thickness e_4 of at least 80 nm.

24. (New) Substrate according to Claim 23, wherein n_1 and/or n_3 are between 1.85 and 2.15, especially between 1.90 and 2.10.

A₁ 25. (New) Substrate according to Claim 23, wherein n_2 and/or n_4 are between 1.35 and 1.55.

26. (New) Substrate according to Claim 23, wherein e_1 is between 5 and 50 nm, especially between 10 and 30 nm or between 15 and 25 nm.

27. (New) Substrate according to Claim 23, wherein e_2 is between 5 and 50 nm, especially between 10 and 35 nm and preferably less than or equal to 30 nm.

28. (New) Substrate according to Claim 23, wherein e_3 is less than or equal to 120 nm and especially at least 75 nm.

29. (New) Substrate according to Claim 23, wherein e_4 is greater than or equal to 80 nm and especially less than or equal to 120 nm.

30. (New) Substrate according to Claim 23, wherein the high-index first layer and the low-index second layer are replaced with a single layer having an intermediate index e_5 of

between 1.65 and 1.80 and preferably having an optical thickness e_{opt} of between 50 and 140 nm, preferably between 85 and 120 nm.

31. (New) Substrate according to claim 30, wherein the intermediate-index layer is based on a mixture of silicon oxide and at least one metal oxide chosen from tin oxide, zinc oxide and titanium oxide, or is based on a silicon oxynitride or oxycarbide and/or on aluminium oxynitride.

32. (New) Substrate according to Claim 23, wherein the high-index first layer and/or the high-index third layer are based on one or more metal oxides chosen from zinc oxide, tin oxide, and zirconium oxide, or based on one or more nitrides chosen from silicon nitride and aluminium nitride.

A, 33. (New) Substrate according to Claim 23, wherein the high-index first layer and/or the high-index third layer include a superposition of several high-index layers, especially a superposition of two layers such as $\text{SnO}_2/\text{Si}_3\text{N}_4$ or $\text{Si}_3\text{N}_4/\text{SnO}_2$.

34. (New) Substrate according to Claim 23, wherein the low-index second layer and/or the low-index fourth layer are based on silicon oxide, silicon oxynitride and/or oxycarbide, or on a mixed silicon aluminium oxide.

35. (New) Substrate according to Claim 23, wherein the substrate is made of clear or bulk-tinted glass.

36. (New) Substrate according to Claim 23, wherein light reflection on a side where the stack of thin layers is provided is reduced by a minimum value of 3 or 4% at an angle of incidence of between 50° and 70° .

37. (New) Substrate according to Claim 23, wherein a colorimetric response of light reflection on a side where the stack of thin layers is provided is such that corresponding a*

42. (New) Glazing according to Claim 39, wherein the other type of antireflection coating is chosen from the following coatings:

a single low-index layer, having an index of less than 1.60 or 1.50, especially about 1.35-1.48, especially based on silicon oxide;

a single layer whose refractive index varies through its thickness, especially of the silicon oxynitride SiO_xN_y type, where x and y vary through its thickness;

a two-layer stack, comprising, in succession, a layer having a high index of at least 1.8, especially made of tin oxide, zinc oxide, zirconium oxide, titanium oxide, silicon nitride or aluminium nitride, and then a layer having a low index, of less than 1.65, especially made of silicon oxide, oxynitride, or oxycarbide;

A,
a three-layer stack comprising, in succession, a layer having a medium index of between 1.65 and 1.8 of the silicon oxycarbide or oxynitride and/or aluminium oxycarbide or oxynitride type, a layer having a high index of greater than 1.9 of the SnO_2 or TiO_2 type, and a layer having a low index of less than 1.65, of the mixed Si-Al oxide or silicon oxide type.

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43. (New) Process for obtaining the glazing according to Claim 39, wherein the antireflection stack or stacks are deposited by sputtering and the optional antireflection coating is deposited by a sol-gel technique, by a pyrolysis technique of CVD or plasma CVD, by sputtering, or by corona discharge.

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44. (New) Application of the glazing according to Claim 39 as interior or exterior glazing for buildings, as a shop display cabinet or counter, which may be curved, as glazing for a vehicle side window, for a vehicle rear window, for a vehicle sunroof, for a vehicle windscreen, or as glazing for protecting objects of the painting, or as an antidazzle computer screen, or as glass furniture.